

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the Application of:

TOSHIBAZU KOBAYASHI

APPLN. NO.: 09/582,483

FILED: JUNE 21, 2000

FOR: ANTISTATIC POLYMER COMPOSITION
AND MOLDINGS THEREOFAssistant Commissioner for Patents
Washington, DC 20231

CASE NO.: AD 6547 US NA

GROUP ART UNIT: 1714

EXAMINER: C. SHOSHO

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DEC 13 2001
TC 1700AMENDMENT

In response to the Office Action dated May 10, 2001, the period for response to which having been extended by three (3) months up to and including November 13, 2001 (Tuesday after Monday Federal Holiday November 12, 2001 and Saturday November 10, 2001) by the accompanying Petition for Extension of Time, please enter the following:

IN THE CLAIMS:

Please enter amended claims 1 and 8 as follows (a marked up version showing changes made is attached hereto):

- 31
1. (amended) An antistatic polymer composition characterized in that it comprises:
- (A) one or more polymers selected from the group consisting of polyester, polycarbonate, polyamide, polyoxymethylene, polyphenylene sulfide, and compounds of polyphenylene oxide and polystyrene;
 - (B) a ion-conductive polyether-based polymer;
 - (C) an ion source comprising: (i) a source of at least one carboxyl group or sulfo group being selected from the group consisting of hydrocarbon acids containing 6-54 carbon atoms, sulfonic acids and organic polymers with at least one carboxyl group or sulfo group; and (ii) a source of at least one metal ion that is